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PATENT Attorney Docket No. 00-103

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applica	ation of: paret S. Fyfield	
Serial No.	09/731,596 (MAR 0 9 2001 (3))	Group Art Unit:
Filed:	December 6, 2000 (PRADEMARK)	Examiner:
For:	Probing Fixture and Method) of Semiconductor Wafer)	

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

Honorable Commissioner of Patents and Trademarks Washington, D.C. 20231

Sir:

The undersigned hereby certifies that the attached Information Disclosure Statement; Form PTO-1449; Certificate of Mailing by First Class Mail; and Return Card, relating to the above application, were deposited as "First Class Mail," with the United States Postal Service, addressed to The Commissioner of Patents and Trademarks, Washington, D.C. 20231, on this 6th day of March, 2001.

Date

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PATENT Attorney Docket No. 00-103

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Margaret S. Fyfield

Serial No. 09/731,596

Filed: December 6, 2000

For: Probing Fixture and Method of

Semiconductor Wafer

Group Art Unit:

Examiner:

INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner of Patents and Trademarks Washington, D.C. 20231

Sir:

The Examiner may wish to consider the following references during the examination of the above-identified application:

Other Documents

Gary Shade and Kendall Scott Wills, *Photoemission Microscopy*, 1997 ASM International, pp. 181-182.

B. Bossmann, P. Baurschmidt, K. Hussey, and E. Black, *Failure Analysis Techniques with the Confocal Laser Scanning Microscope*, ISTFA '92: The 18th International Symposium for Testing & Failure Analysis, October 1992, pp. 351-361

Nevil M. Wu, Kevin Weaver, James H. Lin, *Failure Analysis from Back Side of Die*, ISTFA '96: 22nd International Symposium for Testing and Failure Analysis, November 1996, 7 pages

TW. Joseph, A.L. Berry, B. Bossman, *Infrared Laser Microscopy of Structures on Heavily Doped Silicon*, ISTFA '92: The 18th International Symposium for Testing & Failure Analysis, October 1992, pp. 1-7

D.L. Barton, P. Tangyunyong, J.M. Soden, A.Y. Liang, F.J. Low, A.N. Zaplatin, K. Shivanandan, and G. Donohoe, *Infrared Light Emission from Semiconductor Devices*, Proceedings of the 22nd International Symposium for Testing and Failure Analysis, November 1996, pp. 9-17

Chun-Cheng Tsao, Steven, Kasapi, and Kurt Hurley, Backside waveform probing of CMOS devices using infrared laser at wavelength of 1064 nm, 6 pages

C. Chiang, N. Khurana, D.T. Hurley, and K. Teasdale, *Backside Emission Microscopy for Integrated Circuits on Heavily Doped Substrate*, Proceedings from the 24th International Symposium for Testing and Failure Analysis, November 1998, pp. 447-453

Kendall Scott Wills, Terril Lewis, Greg Billus, Hai Hoang, Optical Beam Induced Current Applications for Failure Analysis of VLSI Devices, 1997 ASM International, pp. 21-26

Yeoh Eng Hong and Martin Tay Tiong We, *The application of novel Failure Analysis Techniques for Advanced Multi-Layered CMOS devices*, 6 pages

T. Koyama, Y. Mashiko, M. Sekine, H. Koyama and K. Horie, *New non-bias optical beam induced current (NB-OBIC) techniques for evaluation of A1 interconnects*, 1995 IEEE, pp. 228-233

Said F. Al-sarawi, *Tape-Automated Bonding*, Centre for High Performance Integrated Technologies and Systems (CHIPTEC), March 1997, pp. 1-2

Said F. Al-sarawi, *Solder Bump Bonding*, Centre for High Performance Integrated Technologies and Systems (CHIPTEC), March 1997, 1 page

Attached is a completed Form PTO-1449 for the Examiner's convenience in citing these references. Copies of the above identified references are also enclosed.

Signed at Greenwood Village, Colorado this 6th day of March, 2001.

Respectfully submitted,

John R. LEX

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FORM PTO-1449 (Rev. 2-82)		U.S. DEPART. OF COMMERCE PATENT AND TRADEMARK OFFICE							ATTY. DOCKET NO. 00-103	SERIAL NO. 09/731,596			
INFORMATION DISCLOSURE STATEMENT BY APPLICANT									APPLICANT Margaret S. Fyfield				
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		Gary Shade and Kendall Scott Wills, Photoemission Microscopy, 1997 ASM International, pp. 181-182.											
		B. Bossmann, P. Baurschmidt, K. Hussey, and E. Black, Failure Analysis Techniques with the Confocal Laser Scanning Microscope, ISTFA '92: The 18 th International Symposium for Testing & Failure Analysis, October 1992, pp. 351-361											
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.